

Tetramethylammonium Hydroxide (TMAH)

Process:

To dissolve remaining photoresist from a wafer or glass substrates using 50-300mL solution.

Materials:

<3% TMAH with 97-98% water solution from the manufacturer (ex. CD-26, MF-319, etc). Lab member provides glass or wafer substrates that is coated with photoresist.

Incompatible Materials:

Plastics, organic solvents, oxidizing agents, and strong acids

Hazards: corrosive on contact, acutely toxic in high concentration. Wash hands after use

Exposure Actions: Do what's below, and then notify CNM2 staff within a few hours. For advice, call CNM2 staff.

Eyes: Hold eyes open in running eyewash station for 15 mins and call 911 as soon as possible

Skin: Remove splashed clothing, wash for 15 minutes and seek medical attention

Personal Protective Equipment:

Wear protective eyewear, double glove or use barrier gloves. If the top glove layer becomes contaminated, immediately discard the top glove and wash hands.

Acceptable Locations For Use:

The photolithography area sinks are the only location available for developer use.

Additional Process Notes:

Use Teflon or glassware for processing materials. User must pour solution into a clean glassware, place sample into the solution for a period of time. Then after pulling the sample from the solution, rinse with DI water and dry with nitrogen. Any deviations from existing processing protocols should be discussed with staff beforehand.

Disposal:

After development, pour solution into disposal bottle labeled "Aqueous Developers" and rinse all glassware in the sink with 3 DI water rinses. **MAKE SURE THE FUNNEL IS CLOSED** after pouring solution into the bottle.